

ALIGNMENT APPARATUS, ALIGNMENT METHOD,  
EXPOSURE APPARATUS AND EXPOSURE METHOD

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ABSTRACT OF THE DISCLOSURE

An alignment apparatus, comprising a position  
detection optical system which detects a position of a  
mark formed on a street line of a substrate and a focus  
detection system which detects deviation between an  
irradiated region and a focused surface of the position  
detection optical system by irradiating a detection light  
on a region of said street line and a different region  
from a region of said mark at a time and detecting a  
reflected light of the detection light.